Applicant: Taketomi Asami et al. Attorney's Docket No.: 12732-061002 / US5111D1

Serial No.: New Divisional Application

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Amendments to the Specification:

Beginning at page 1, line 2, please insert the following paragraph:

CROSS-REFERENCE TO RELATED APPLICATIONS

This application is a divisional application of U.S. Application Serial No. 09/918,547, Fat. 6, 703, 215
filed on August 1, 2001, now allowed, which claims priority from, and is a continuation-in-part of, U.S. Application No. 09/880,089 (U.S. Patent Publication No. US-2002-0043662 A1), filed pat. 6,28,537
June 14, 2001 and which claims the benefit of a foreign priority application filed in Japan on August 2, 2000, as Serial No. 2000-234913. This application claims priority all of these applications, and all of these applications are incorporated by reference.

Please replace the paragraph beginning at page 1, line 17 as with the following amended paragraph:

A technique has been developed for manufacturing a thin film transistor (hereinafter referred to as TFT) from a semiconductor film that has a polycrystal structure (the film is hereinafter referred to as crystalline semiconductor film) and is formed on a glass, [[quarts]] quartz or other substrate. A TFT formed from a crystalline semiconductor film is applied to flat panel displays, typically, liquid crystal display devices, as measures for realizing high definition image display, and is applied to monolithic displays in which a pixel portion and an integrated circuit necessary to drive the pixel portion are formed on the same substrate, as measures for realizing it.

Please replace the paragraph beginning at page 2, line 6 as with the following amended paragraph:

A crystalline semiconductor film can have a polycrystal structure if it is obtained by subjecting an amorphous semiconductor film formed on a glass, [[quarts]] quartz or other substrate to heat treatment or laser light irradiation for crystallization. Crystallization is known to progress from a crystal nuclear spontaneously generated in the interface between the amorphous semiconductor film and the substrate. While crystal grains in a polycrystal